



**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In Patent Application of

SHIMIZU et al

Atty. Ref.: 829-619; Confirmation No. 2644

Appl. No. 10/735,621

TC/A.U. 1763

Filed: December 16, 2003

Examiner: Arancibia, Maureen G.

For: PLASMA CVD APPARATUS, AND METHOD FOR FORMING FILM AND METHOD  
FOR FORMING SEMICONDUCTOR DEVICE USING THE SAME

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June 20, 2006

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**AMENDMENT AFTER FINAL**

Responsive to the Official Action dated March 21, 2006, reconsideration is respectfully requested for at least the following reasons (*note that this amendment should be entered because the only change to the claims is a correction of a typographical error in claim 12*).